

## IN THE CLAIMS

Claims 18-26 have been Canceled

1. (Original) A method, comprising:  
analyzing a sacrificial material sample by high performance liquid chromatography;  
and  
identifying chemical markers that correlate with material contaminants in the  
sacrificial material.
2. (Original) The method of claim 1, wherein the sacrificial material sample comprises a  
sacrificial light absorbing material.
3. (Original) The method of claim 2, further comprising identifying chemical markers  
that correlate with a degradation of the sacrificial light absorbing material.
4. (Original) The method of claim 1, wherein identifying further comprises detecting  
the chemical markers with an ultraviolet/visual and mass spectroscopy system.
5. (Original) The method of claim 4, wherein the ultraviolet/visual and mass  
spectroscopy system has a monitoring wavelength of about 240 nanometers to about 260  
nanometers.
6. (Original) The method of claim 2, wherein analyzing further comprises:  
providing an eluent having a methanol and water mixture; and  
flowing the eluent at a rate from about 0.3 to about 1.0 ml/min
7. (Original) The method of claim 2, wherein identifying further comprises providing an  
analytical column having a length of about 5 centimeters to about 25 centimeters in length.
8. (Original) The method of claim 3, wherein identifying further comprises;  
analyzing the sacrificial light absorbing material a first time to generate a first signal;

analyzing the sacrificial light absorbing material a second time to generate a second signal; and

comparing the first signal to the second signal.

9. (Original) The method of claim 1, wherein the sacrificial material sample comprises a spin-on-glass material.

10. (Original) The method of claim 1, wherein analyzing the sacrificial material is done prior to use of the sacrificial material during semiconductor fabrication in process.

11. (Original) A method, comprising:

performing a first analysis of a sacrificial light absorbing material by high performance liquid chromatography;

performing a second analysis of the sacrificial light absorbing material by high performance liquid chromatography; and

identifying chemical markers correlating with a degraded sacrificial light absorbing material.

12. (Original) The method of claim 11, wherein identifying further comprises detecting the chemical markers with an ultraviolet/visual and mass spectroscopy system.

13. (Original) The method of claim 12, wherein the ultraviolet/visual and mass spectroscopy system has a monitoring wavelength of about 240 nanometers to about 260 nanometers.

14. (Original) The method of claim 11, wherein identifying further comprises comparing a first signal from the first analysis with a second signal from the second analysis.

15. (Original) The method of claim 12, wherein the second analysis is done within ten days of the first analysis.

16. (Original) The method of claim 11, wherein analyzing the first and second analysis of

the sacrificial light absorbing material is done prior to use of the sacrificial light absorbing material during semiconductor fabrication in process.

17. (Original) The method of claim 14, wherein the sacrificial light absorbing material comprises spin-on-glass material.

18. – 26 (Canceled)